



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:
Chen et al.

Serial No. 10/712,460

Filed: 11/13/2003

For: Semiconductor Wafer
Manufacturing Methods
Employing Cleaning Delay Period

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Group Art Unit: 1746

Examiner: To be determined

Customer No.: 000042717

Attorney Docket No.:
TSMC2002-1015/24061.42

PRELIMINARY AMENDMENT

Mail Stop Amendment
Commissioner For Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination, please amend the above-identified patent application as follows:

Amendments to the Specification begin on page 2 of this paper.

Remarks begin on page 3 of this paper.